

Notice of References Cited

Application/Control No.
10/629,271

Applicant(s)/Patent Under
Reexamination
WONG ET AL.

Examiner
Craig A. Thompson

Art Unit
2813

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-RE34,887	03-1995	Ushifusa et al.	361/795
*	B	US-2002/0090514	07-2002	Leroux et al.	428/406
*	C	US-6,110,649	08-2000	Carter et al.	430/313
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	N	JP 2003017481 A	01-2003	Japan	KITO, NOBUHIRO	H01L 21/316
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Bae et al. Derwent Abstracted Publication No. KR2002007774A "Ceramic hollow microsphere production" 22 July 2003
	V	Lodel Nitt KK Derwent Abstracted Publication No. JP2003017481A "Low dielectric constant insulating film material for semiconductor device, includes hollow microsphere element"
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.